

PATENT ABSTRACTS OF JAPAN

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(21)Application number : 11-266030 (71)Applicant : SEKISUI CHEM CO LTD

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(54) METHOD FOR PRODUCING POLYVINYL ACETAL RESIN

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a method for producing an excellent polyvinyl acetal resin having low content of impure electrolytes by which an incorporation of a neutralized salt or the like generated in the process of neutralizing an acid catalyst in the polyvinyl acetal resin slurry generated by condensation reaction of polyvinyl alcohol with aldehydes in the presence of the acid catalyst in an aqueous phase into particles thereof can be suppressed.

SOLUTION: The method for producing the polyvinyl acetal resin is the one of neutralizing and washing the polyvinyl acetal resin product obtained by carrying out the condensation reaction of the polyvinyl alcohol with the aldehydes in the presence of the acid catalyst in the aqueous phase and the steps of the neutralization and washing is carried out repeatedly in plural times. The first time of the neutralizing reaction is simultaneously carried out with the time when the temperature of the obtained polyvinyl acetal resin product reaches glass-transition temperature.

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